



Pending

Active

L1: (2) "6117750"

L2: (412523) semiconductor and substrate

L3: (101) L2 and (threading adj dislocation)

Failed

(27) (((semiconductor and gate) and isotropic) and (not a

(213) (((semiconductor and gate) and isotropic) and (not a

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L2 and (threading adj dislocation)

	U	S1	Document ID	Issue Date	Pages	Title	Current OR	Current XRef
1	<input type="checkbox"/>	<input type="checkbox"/>	US 20010040246		23	GaN field-effect transistor and method of manufacturing the same		
2	<input type="checkbox"/>	<input type="checkbox"/>	A1		10	Relaxed InGaAs buffers		
3	<input type="checkbox"/>	<input type="checkbox"/>	US 20010039104		29	Semiconductor substrate, light-emitting device, and method for		
4	<input type="checkbox"/>	<input type="checkbox"/>	A1		10	Method for fabricating silicon-on-insulator material		
5	<input type="checkbox"/>	<input type="checkbox"/>	US 20010031385		11	Group III-V compound semiconductor and method of produ		
6	<input type="checkbox"/>	<input type="checkbox"/>	A1		30	Nitride compound semiconductor		
7	<input type="checkbox"/>	<input type="checkbox"/>	US 20010026873		10	light emitting device and method for		
8	<input type="checkbox"/>	<input type="checkbox"/>	A1		10	METHOD FOR PRODUCING HIGH QUALITY HETEROEPITAX		
9	<input type="checkbox"/>	<input type="checkbox"/>	US 20010024884		10	Low threading dislocation density		
10	<input checked="" type="checkbox"/>	<input type="checkbox"/>	A1		11	relaxed mismatched epilayers without		
	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 20010023946		31	Crystal growth method for nitride		
	<input checked="" type="checkbox"/>	<input type="checkbox"/>	A1			semiconductor, nitride semiconductor		
	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 20010012678			Method for the formation of		
	<input checked="" type="checkbox"/>	<input type="checkbox"/>	A1			semiconductor layer		

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Active Failed

L1: (2) "6117750"
 L2: (412523) semiconductor and substrate
 L3: (101) L2 and (threading adj dislocation)
 L4: (27) ((semiconductor and substrate) and lattice-mism

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Default operator: OR Highlight all hit terms initially

((semiconductor and substrate) and lattice-mismatched)
and multilayer

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	U	I	Document ID	Issue Date	Pages	Title	Current OR	Current XRef
1	<input type="checkbox"/>	<input checked="" type="checkbox"/>	US 20010038655 A1		39	Semiconductor devices		
2	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6239354 B1	20010529	7	Electrical isolation of component cells in monolithically interconnected	136/249	136/244
3	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6222200 B1	20010424	13	Photodetector with spectrally extended responsivity	257/18	257/185
4	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6111276 A	20000829	8	Semiconductor device structures incorporating "buried" mirrors and/or	257/98	136/259
5	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 6010937 A	20000104	10	Reduction of dislocations in a heteroepitaxial semiconductor structu	438/363	438/413
6	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5953356 A	19990914	18	Intersubband quantum box semiconductor laser	372/45	372/43
7	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5912913 A	19990615	20	Vertical cavity surface emitting laser, optical transmitter-receiver	372/45	372/46
8	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5883911 A	19990316	7	Surface-emitting laser device	372/45	372/96
9	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5874747 A	19990223	31	High brightness electroluminescent device emitting in the green to	257/77	257/103
10	<input checked="" type="checkbox"/>	<input type="checkbox"/>	US 5856206 A	19990105	6	Method for fabricating bragg reflector using in situ laser reflectometry	438/32	118/715

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